

Supporting Information

Innovative Scheme for Sub-50 nm Patterning via Electrohydrodynamic Lithography

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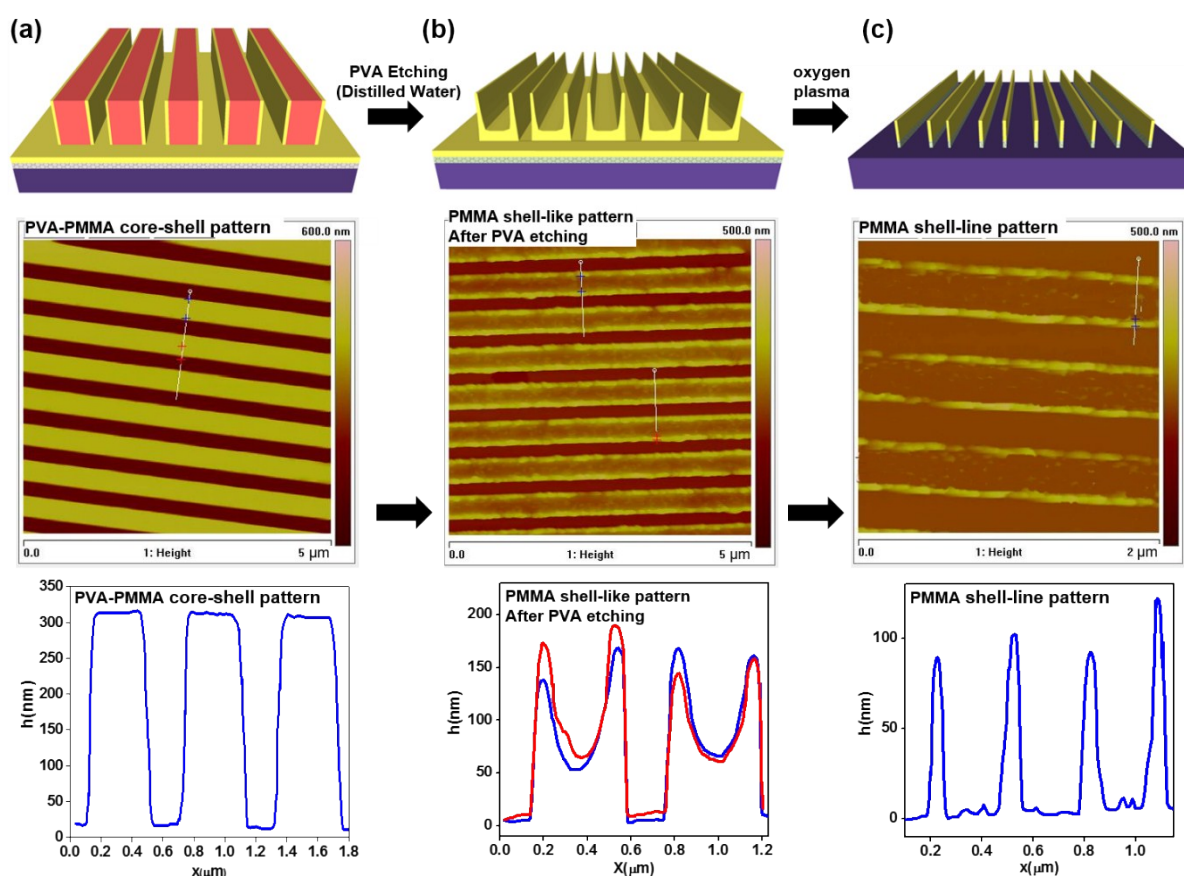


Fig. S1. Schematic representation and AFM profiles of the etching process of PVA. (a) PVA-PMMA core-shell-like nanostructure with a width of 300 nm and a height of 300 nm. (b) PMMA shell-like structure after the removal of the PVA core pattern using distilled water. (c) Remaining PMMA shell pattern after the oxygen plasma process.